



IAP12 Rec'd PCT/PTO 10 MAY 2007  
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Shuichi OKAWA et al.

Application No.: New U.S. National Stage of  
PCT/JP04/008232

Filed: October 17, 2005

Docket No.: 125685

For: MASK MATERIAL FOR REACTIVE ION ETCHING, MASK, AND DRY ETCHING  
METHOD

**RESPONSE TO NOTICE OF NON-COMPLIANT AMENDMENT (37 CFR 1.121) &**  
**CORRECTED AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In reply to Notice of Non-Compliant Amendment mailed May 2, 2007, please  
consider the following:

**Amendments to the Claims** as reflected in the listing of claims; and

**Remarks.**